



भाभा परमाणु अनुसंधान केंद्र
BHABHA ATOMIC RESEARCH CENTRE

mp Micropack Limited
macro quality in micro circuitry



Single Mask GEM foil development in India

Updated : 25th Oct 2014

L. M. Pant¹, A. K. Mohanty¹, O. J. Pinto², S. Gadhadharan², Pradeep Menon²,
Archana Sharma³, Rui De Oliveira³

¹*Nuclear Physics Division, Bhabha Atomic Research Centre, Mumbai*

²*Micropack Limited, Bengaluru, 560105, India*

³*CERN, Geneva, Switzerland*

The Triple GEM for the CMS Muon System

Rate capability : 10^5 Hz/cm^2

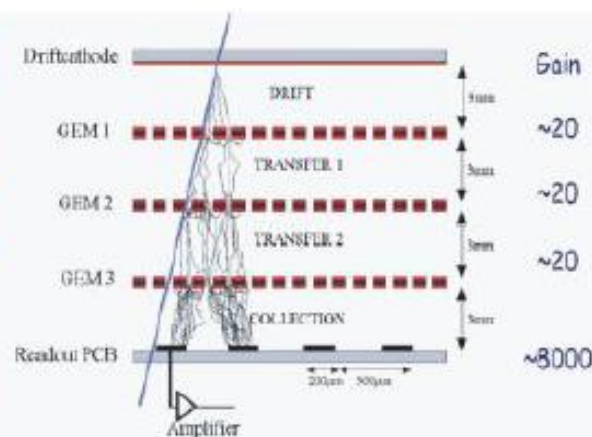
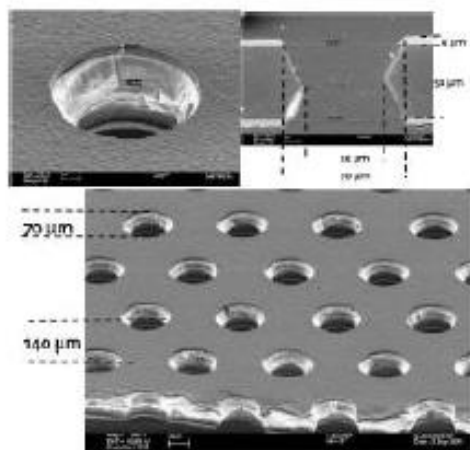
Spatial/Time resolution: $\sim 100 \mu\text{m} / \sim 4\text{-}5 \text{ ns}$

Efficiency $> 98\%$

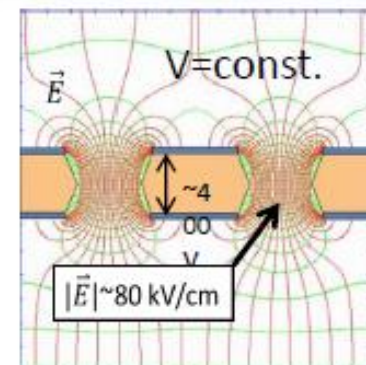
Gas Mixture: Ar-CO₂-CF₄ (non flammable mixture)

➤ Combine triggering and tracking functions

➤ Enhance and optimize the readout (η - ϕ) granularity by improved rate capability



- GEM foils developed using PCB manufacturing techniques
- Large areas $\sim 1 \text{ m} \times 2 \text{ m}$ with industrial processes (cost eff.)
- Each foil (perforated with holes) is $50 \mu\text{m}$ kapton sheet with copper coated sides ($5 \mu\text{m}$)
- Typical hole dimensions : Diameter = $70 \mu\text{m}$, Pitch = $140 \mu\text{m}$,
- Long term (10 years) operation experience in Compass, and more recently LHCb and TOTEM



- **100% privately owned Indian company**
- **Focus on small volume / high mix segment**
- **Factory is located at Jigani Industrial Area, in Bangalore, in 10 acres of land with a built-up manufacturing area of 60000 Sq ft.**
- **170 employees, all technically qualified and trained to handle specialized processes**
- **Presently manufacturing multilayer rigid PCBs up to 30 layers.**
- **Fabricates approximately 450-500 designs every month including 300-350 fresh designs.**
- **In-house facility for all operations**

- **Markets segments catered –**
Aerospace / Defence, Industrial Electronics / Prototype /
Technology oriented projects with new materials / processes
- **Product & System Approvals -**
MIL 55110 / MIL 50884 / AS9100 – ISO9001-2008 / ISO 14001
- **Customer Approvals –**
ISRO / Goodrich Aerospace (UTAS) / BEL / HAL / NPCIL
- **Product Range –**
Multilayer Rigid PCBs - Heat Sink / Impedance controlled /
Blind and buried via PCBs, Rigid Flex PCBs, Flexible PCBs,
Teflon PCBs

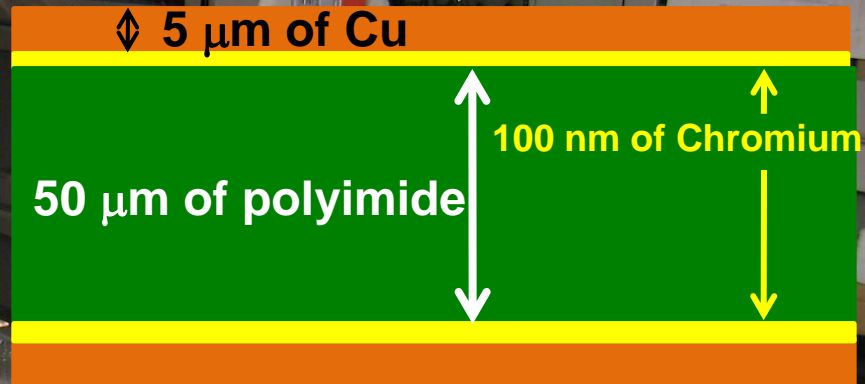
ROADMAP

S.No.	Item	1Q			2Q			3Q			4Q			1Q			2Q			3Q			4Q		
		2	3	4	5	6	7	8	9	10	11	12	1	2	3	4	5	6	7	8	9	10	11	12	
1	License Agreement	→																							
2	100 x 100 Fabrication and QC Validation																								
	- Rebuild equipments/utility for GEM Foil	→																							
	- Prepare raw materials(FCCL, mixed chemicals)	→																							
	- develop the <i>prototype</i>	→																							
	- QC validate the prototype @COMPANY	→																							
	- QC validate the prototype @COMPANY	→																							
3	100 x 100 Routine and standard production , 300 x 300 R&D																								
	- <i>100 x 100 routine</i> & standard production	→																							
	- develop the <i>prototype of 300 x 300</i>	→																							
	- QC validate the prototype @COMPANY/CERN	→																							
4	300 x 300 Routine and standard production , 500 x 500 R&D																								
	- <i>300 x 300 routine</i> & standard production	→																							
	- develop the <i>prototype of 500 x 500</i>	→																							
	- QC validate the prototype @COMPANY/CERN	→																							

- **ToT signed and agreed between CERN and Micropack Ltd., India : Jan 2014 for Single Mask GEM foil fabrication**
- **5 micron Cu clad polyimide foils received from CERN via BARC**
- **15 microns photoresist sourced from Korea**
- **Augmentation of resources for trial runs for the first 5 cm x 5 cm GEM foil (initial trials) with 200 microns / 400 micron pitch in progress :**

The Cu clad polyimide (5:50:5) from Korea via CERN (need to have an independent supply)

July 2014

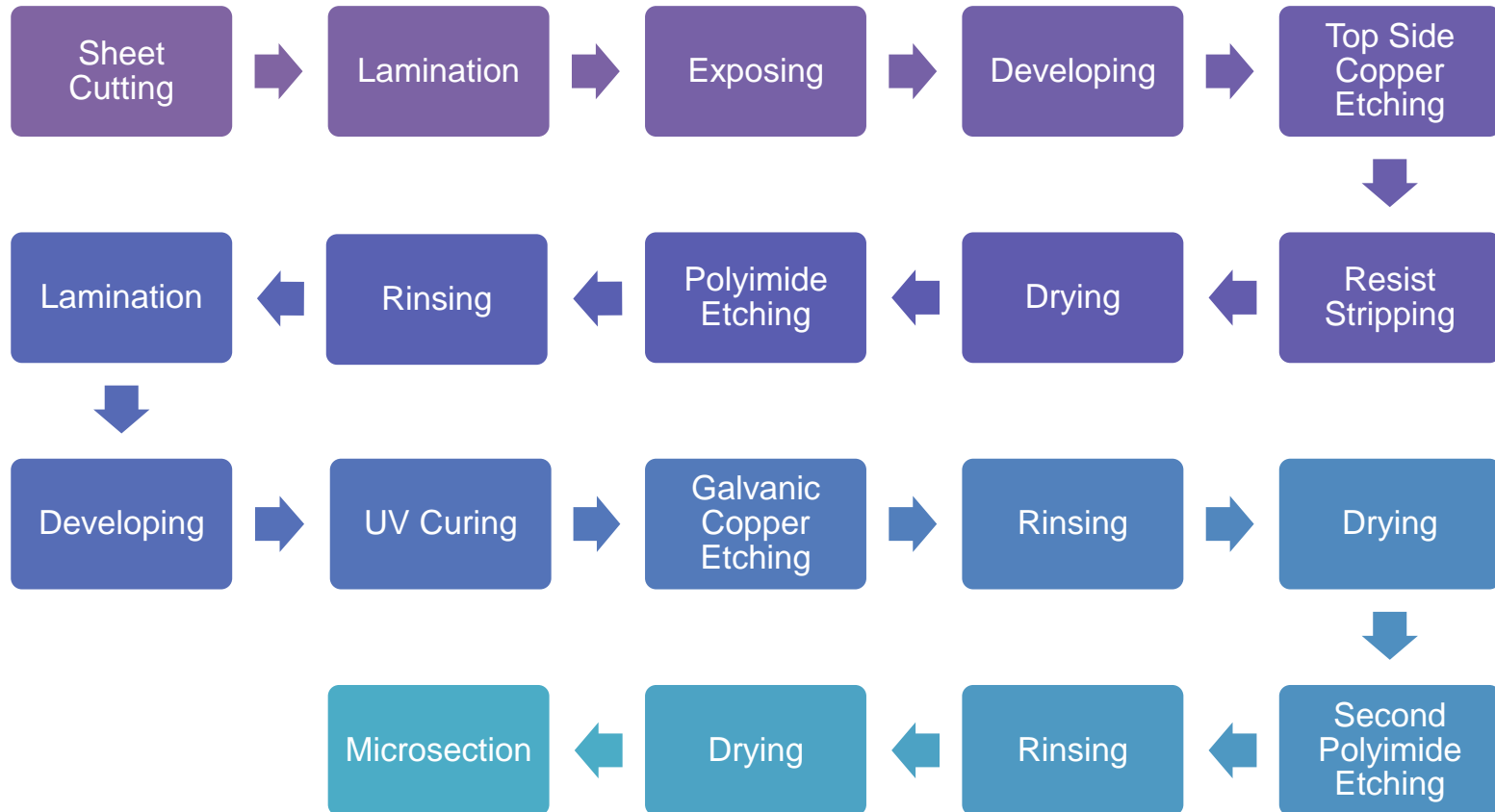


arrived from CERN on 14th July 2014



dispatched to Micropack on 16th July 14

- **Project target – GEM Foils with 70 μm diameter holes at 140 μm pitch of 10cm x 10cm / 30cm x 30cm**
- **Initiated trials with of 5cm x 5cm**
- **Image transfer of 70microns / 140 microns well within the capability**
- **Process concerns in Polyimide etching and reverse copper etching**
- **SS 306 tanks for Polyimide etching is fabricated. Includes heaters/ circulation pump / exhaust lips**
- **BARC personnel visited Micropack on 11 Sep, to freeze the action plan**
- **Mr. Rui from CERN visited BARC & Micropack in October 2014**

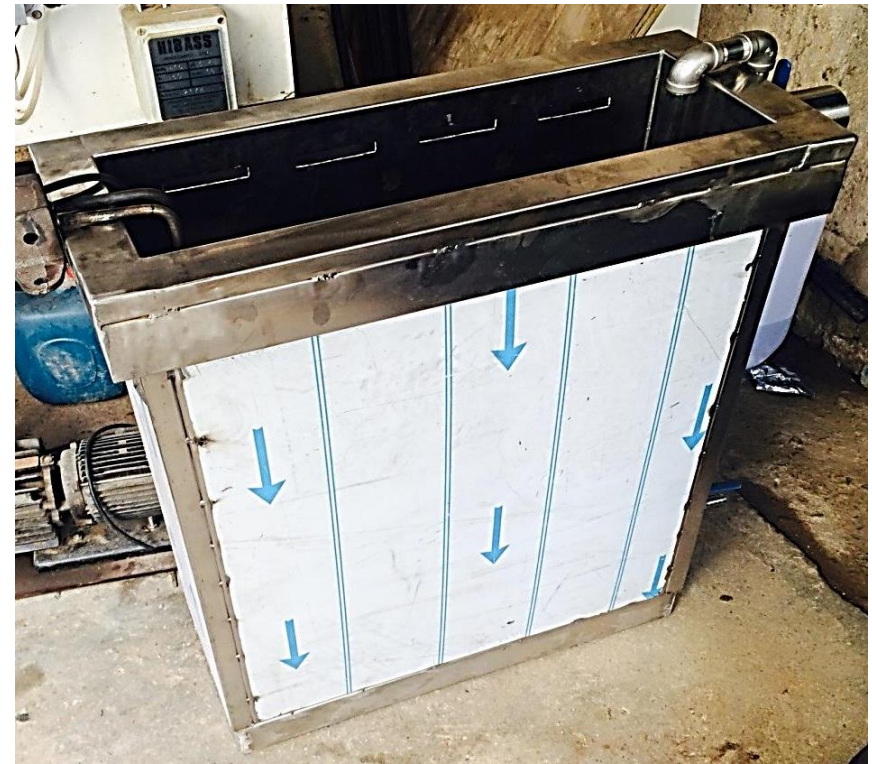
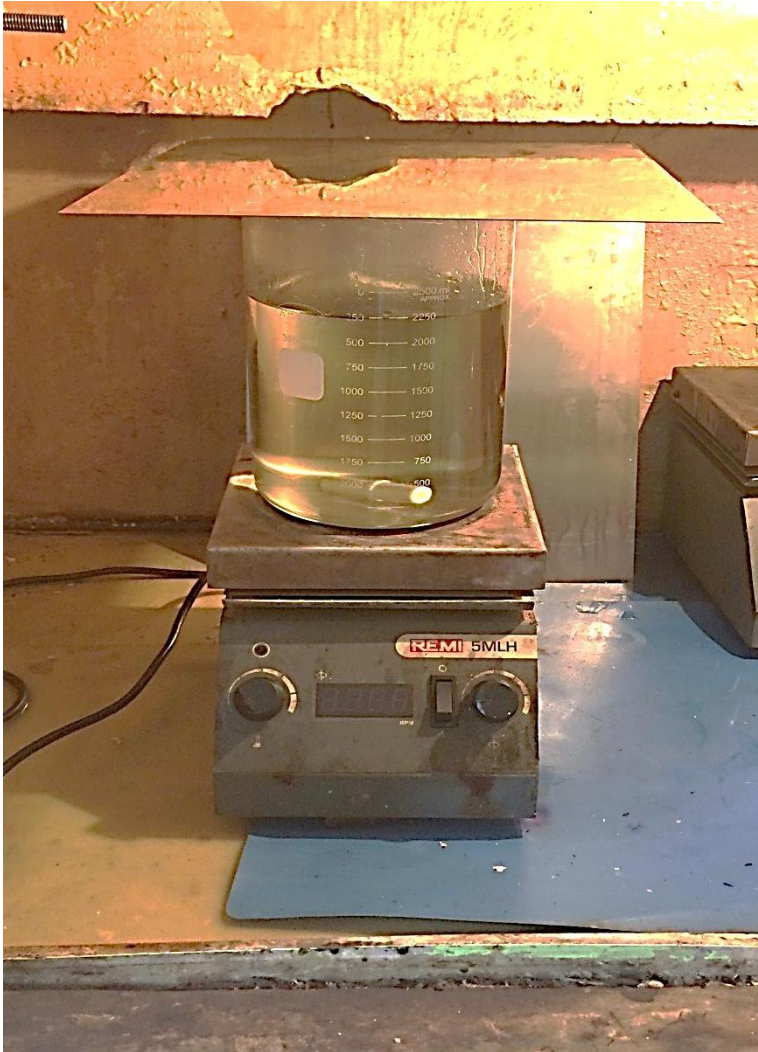




Collimated UV Exposure



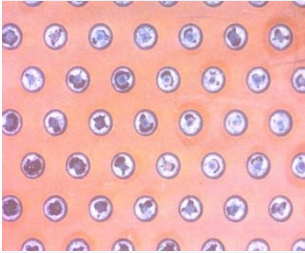

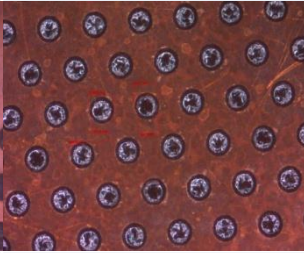
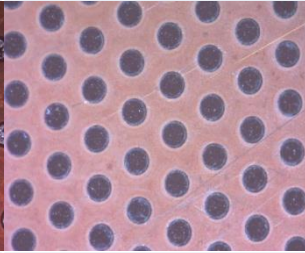
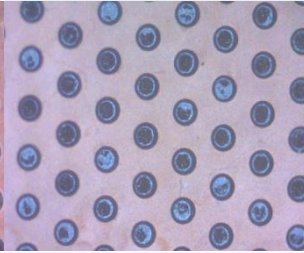
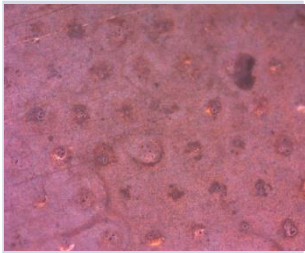
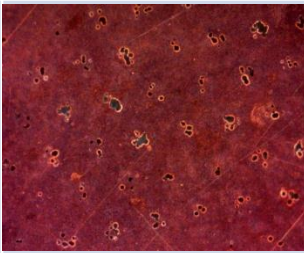
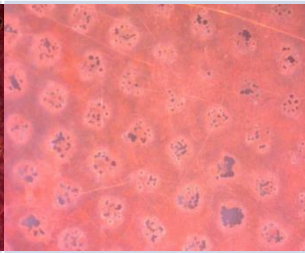
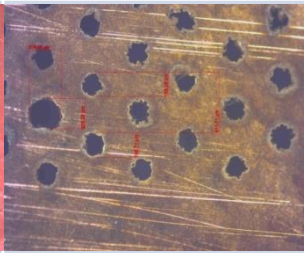


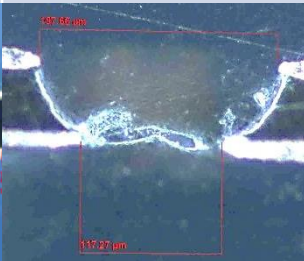

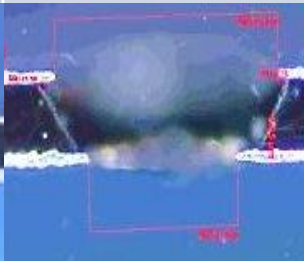
Acid Etcher

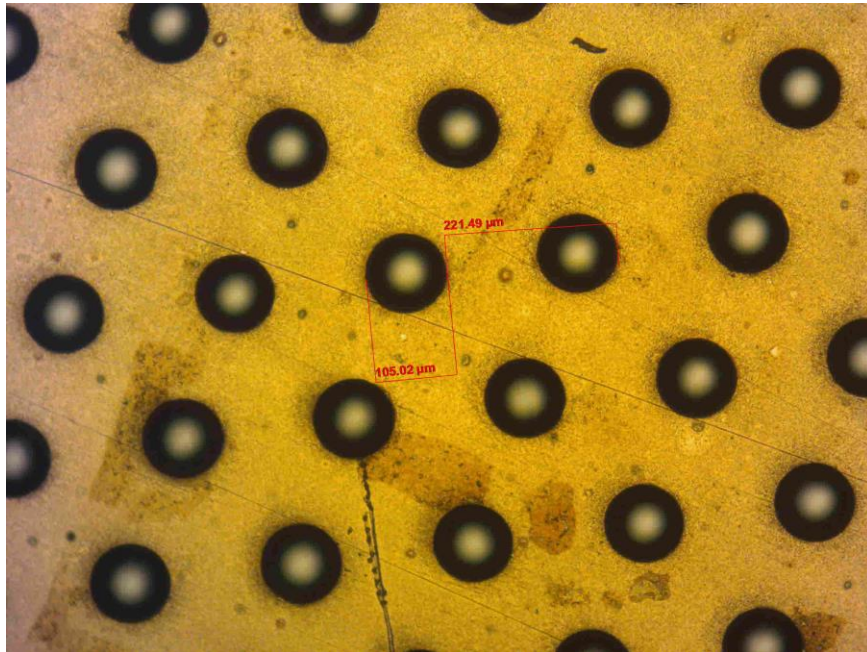


- The left image shows our current lab scale setup being used for the trials
- Top image is the SS 306 tank for Polyimide etching which was fabricated and is at the factory

Trial Summary (all 200 microns dia / 400 microns pitch)

mp

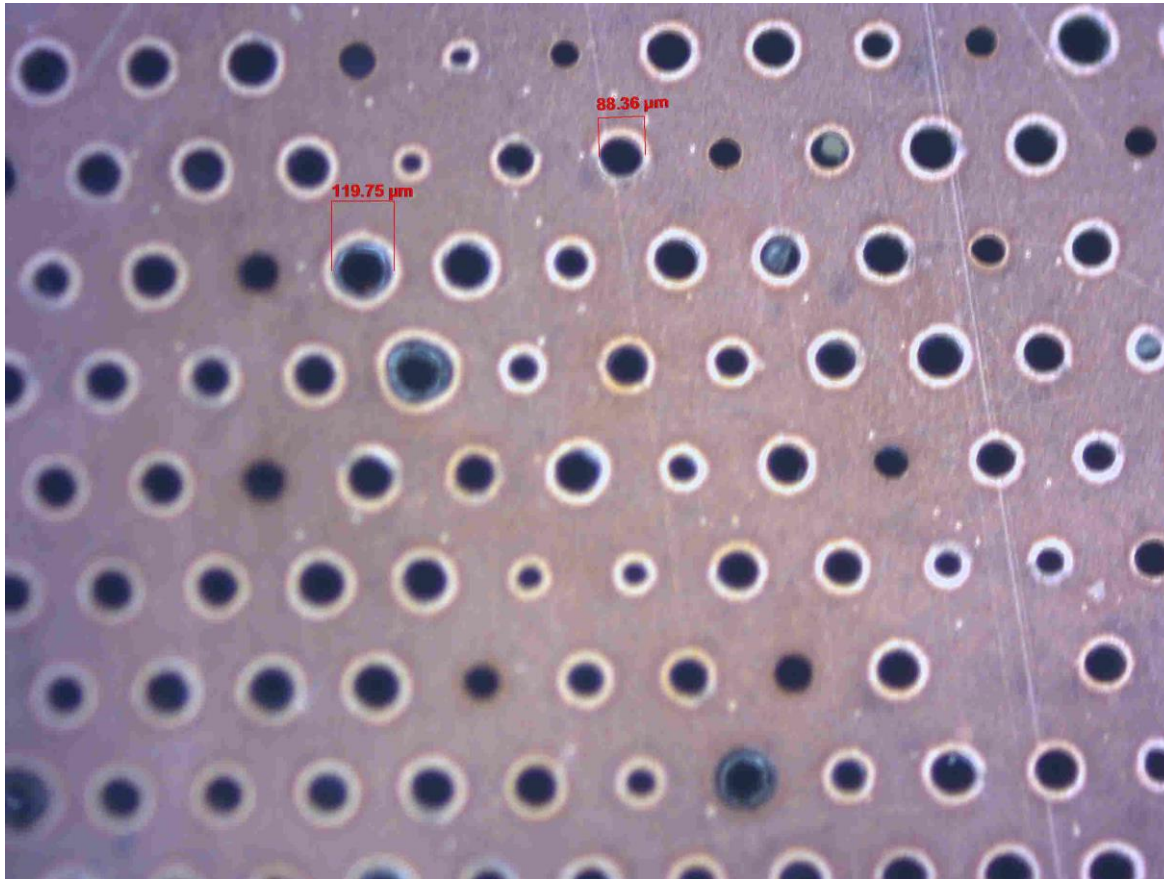
	Trial 1	Trial 2	Trial 3	Trial 4	Trial 5
Time Period	July – 3 rd Week	August – 2 nd Week	September – 1 st Week	September – 3 rd Week	October – 1 st Week
Polyimide Etching					
Reverse Copper Etching		NO IMAGE			
Micro Section Image					



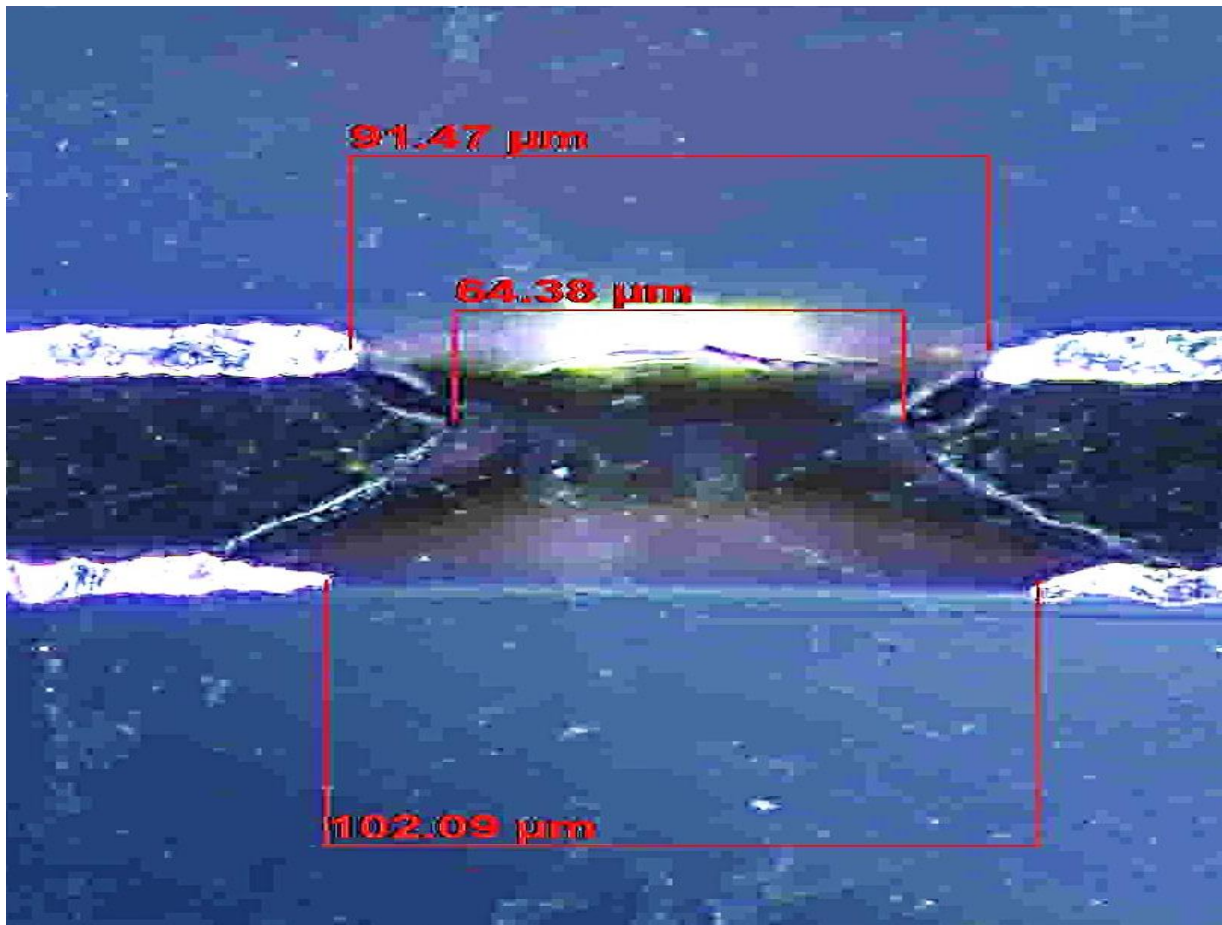
- Trials with 100 microns dia / 200 microns pitch
- Taper in Polyimide etching observed
- The diameter obtained at the top of the hole was measured at 105.02 μ
- The diameter obtained at the bottom of the hole was measured at 34.72 μ
- The pitch obtained between the holes was measured at 221.49 μ

Trial 6 – Galvanic Copper Etching

mp



- Copper removal seen on the bottom side
- However, uniformity of hole opening was not obtained.
- A maximum hole diameter of 119.75μ was obtained
- A minimum hole diameter of 88.36μ was obtained
- No opening was obtained at 10-12 locations (total of 12000 holes) , possibly due to incomplete removal of polyimide



•The bi-conical structure was obtained

Location	Diameter
Top	102.09μ
Throat	64.38μ
Bottom	91.47μ

•Over-Etching of polyimide was observed due longer dip time during polyimide etching

Project Outlook:

- Trials to be continued with process modifications based on the learning from each trials
- Process modifications suggested by Mr. Rui to be tried within the next 3 weeks
- Trial results to be shared with BARC / CERN on a weekly basis for suggestions / process improvements

Micropack is committed to achieve the goal of realizing Single mask GEM foils in India and will strive to continuously improve the process / align resources to meet this objective.

Thank You